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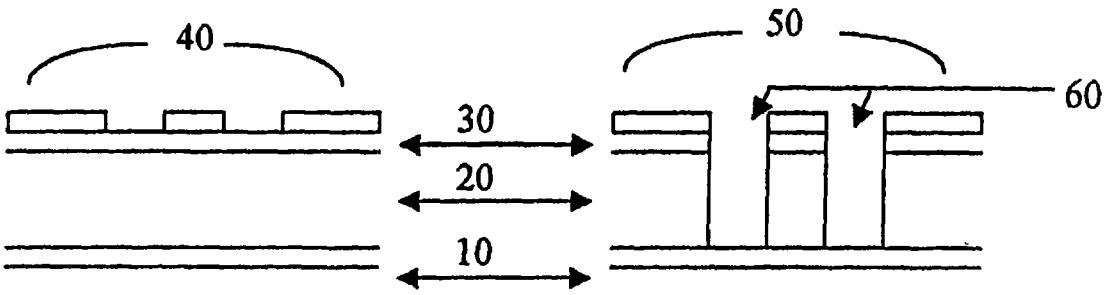
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(54) Title: METHOD TO RESTORE HYDROPHOBICITY IN DIELECTRIC FILMS AND MATERIALS



(57) Abstract: Silica dielectric films, whether nonporous foamed silica dielectrics or nonporous silica dielectrics are readily damaged by fabrication methods and reagents that reduce or remove hydrophobic properties from the dielectric surface The invention provides for methods of imparting hydrophobic properties to such damaged silica dielectric films present on a substrate. The invention also provides plasma-based methods for imparting hydrophobicity to both new and damaged silica dielectric films. Semiconductor devices prepared by the inventive processes are also provided.

WO 02/01621 A2